UCD DUBLIN

2010 International Workshop on Extreme Ultraviolet Sources

University College Dublin
November 13 - 15, 2010

• Final Call for Papers •

This new annual workshop will focus on wavelengths of 13.5 nm or less for next generation EUV sources, as well as technology for high-brightness metrology sources at 13.5 nm to support extreme ultraviolet lithography (EUVL). Potential applications of EUV sources in non-EUVL areas also will be discussed. The workshop will include papers on EUVL and soft X-ray sources. Papers on high power EUV sources at 13.5 nm to support commercial EUVL applications are also welcome. Theoretical as well as experimental approaches will be accepted.

Abstracts of 200 words or fewer should be sent to abstracts@euvlitho.com by the deadline. Please indicate whether an oral presentation or poster session is preferred, and include each author's full name, e-mail address, affiliation and mailing address.

This workshop will provide a forum for researchers in the EUV and soft X-ray areas to present their work and discuss potential applications of their technology. Student papers are highly encouraged. Researchers in the EUV and soft X-ray source areas will find this workshop valuable, as will end-users of EUV and soft X-ray sources. The workshop proceedings will be published online.

The EUVL Workshop is organized by University College Dublin (UCD) with the support of EUV Litho, Inc. For sponsorship opportunities, please contact Dr. Padraig Dunne at padraig.dunne@ucd.ie.

Deadlines

Abstract Submission
October 1, 2010

Author Notification
October 8, 2010

Abstract Submission

abstracts@euvlitho.com

Contact

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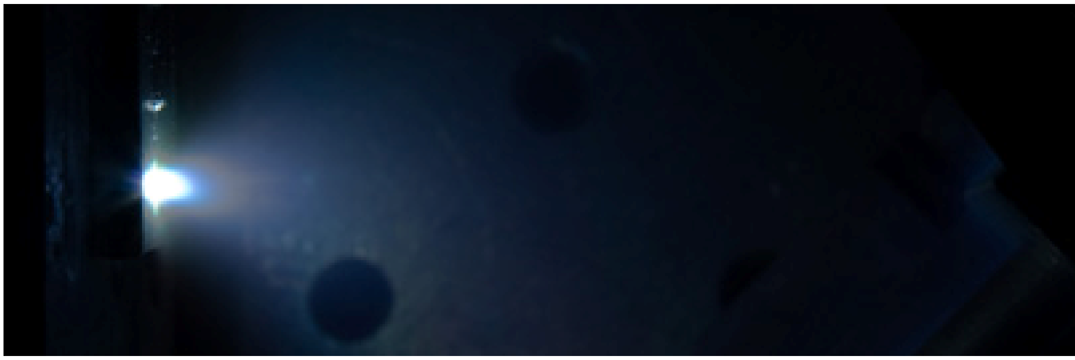
Registration and Travel

Information Coming Soon at

www.euvlitho.com



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